

REMARKS

Claims 1-2 and 5-6 are pending in this application. By this Amendment, claims 1 and 5 are amended. No new matter is added. Reconsideration of this application is respectfully requested.

The Office Action rejects claims 1-2 and 5-6 under 35 U.S.C. §103(a) over U.S. Patent No. 5,648,276 to Hara et al. ("Hara") in view of U.S. Patent Application Publication No. 2002/0129902 to Babayan et al. ("Babayan") and further in view of U.S. Patent No. 5,532,190 to Goodyear et al. ("Goodyear"). The rejection is respectfully traversed.

Claim 1 recites a CVD system " wherein . . . radicals in the plasma are introduced into the film deposition chamber from the plasma generator **via through holes of said lower plate that are distributed across said lower plate.** . . . [the] lower plate further including **a plurality of diffusion holes that are distributed across said lower plate and interspersed with said through holes, whereby a surface area of said lower plate includes an interspersed distribution of both diffusion holes and through holes,** and said material gas is directly supplied into the film deposition chamber through said plurality of diffusion holes to react with said radicals supplied through said through holes in the film deposition chamber."

Support for this feature may be found throughout the original specification and drawings. For example, specific support may be found at least page 9, lines 2-13; page 10, lines 14-21; and Fig. 2.

None of the cited references teach such a feature. Therefore, even if combined, the Hara/Babayan/Goodyear combination would not have resulted in, nor suggested to one of ordinary skill in the art at the time the invention was made, the combinations of features recited in the claims.

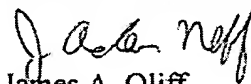
Accordingly, it is respectfully submitted that claim 1 is patentably distinguishable from the cited references for at least the reasons addressed above. Claim 5 includes features similar to claim 1 and, therefore, is patentably distinguishable from the cited references for at least the same reasons. Claims 2 and 6 depend from claims 1 and 5, respectively, and are likewise patentably distinguishable over the applied art for at least their dependence on allowable base claims, as well as for additional features they recite. Accordingly, withdrawal of this rejection is respectfully requested.

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In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1-2 and 5-6 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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